

Title (en)
Positive resist composition and method of pattern formation with the same

Title (de)
Positive Resistzusammensetzung und Verfahren zur Strukturformung damit

Title (fr)
Composition de réserve positive et procédé de formation de motif avec celle-ci

Publication
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Application
EP 08165715 A 20060725

Priority

- EP 06015449 A 20060725
- JP 2005215412 A 20050726
- JP 2005356714 A 20051209
- JP 2006007762 A 20060116
- JP 2006107727 A 20060410
- JP 2006198897 A 20060721

Abstract (en)
[origin: EP1754999A2] A positive resist composition comprising: (A) a resin which comes to have an enhanced solubility in an alkaline developing solution by an action of an acid; (B) a compound which generates an acid upon irradiation with actinic rays or a radiation; (C) a fluorine-containing compound containing at least one group selected from the groups (x) to (z); and (F) a solvent, and a method of pattern formation with the composition: (x) an alkali-soluble group; (y) a group which decomposes by an action of an alkaline developing solution to enhance a solubility in an alkaline developing solution; and (z) a group which decomposes by an action of an acid.

IPC 8 full level
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CPC (source: EP KR US)
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Citation (examination)

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- TAKECHI S ET AL: "IMPACT OF 2-METHYL-2-ADAMANTYL GROUP USED FOR 193-NM SINGLE-LAYER RESIST", JOURNAL OF PHOTOPOLYMER SCIENCE AND TECHNOLOGY, TECHNICAL ASSOCIATION OF PHOTOPOLYMERS JAPAN, JP, vol. 9, no. 3, 1 January 1996 (1996-01-01), pages 475 - 487, XP008017679, ISSN: 0914-9244

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